





## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Geun Su Lee

Serial No.: 10/718,959

Filed:

November 21, 2003

Title:

PHOTORESIST POLYMER

AND PHOTORESIST

**COMPOSITION CONTAINING** 

THE SAME

Group Art Unit:

1752

Examiner: Sin J. Lee

Attorney Docket No.: 30205/39514

I hereby certify that this paper is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, Virginia 22313-1450, on January 23, 2006.

ándíp H. Patel (Reg. No. 43,848)

Attorney for Applicant

## **AMENDMENT "C" AND RESPONSE TO OFFICIAL ACTION**

Mail Stop Amendment **Commissioner for Patents** P.O. Box 1450 Alexandria, Virginia 22313-1450

Dear Sir:

In response to the non-final official action dated October 28, 2005, please amend the above-identified patent application as set forth herein.

Amendments to the claims begin on page 2 of this paper.

Remarks begin on page 9 of this paper.